

**Amendments to the Claims**

The listing of claims will replace all prior version, and listings, of claims in the application.

**Listing of Claims**

Claim 1 (Currently Amended). A measuring system of a gas-stream environment, said measuring system of a gas-stream environment comprising:

a stage, said stage is located on a transport apparatus and a wafer placed on said stage;

a datum platen, said datum platen is located on said transport apparatus and on stage to place a datum slice, wherein said datum slice to be the measuring reference point;

a lens, said lens is located above said stage that is used to measure the thickness of said wafer and said datum slice;

a gas supplier, said gas supplier is used to supply a gas;

a first gas nozzle, said first gas nozzle is located on a side of said datum platen;

a second gas nozzle, said second gas nozzle is located on a side of said stage;

a first tube, said first tube is connected with said first gas nozzle and said gas supplier;

a second tube, said second tube is connected with said second gas nozzle and with said gas supplier, wherein said gas supplier must be opened to supplied make said gas that passed through said first tube and said second tube, and exhausted from said first gas nozzle and said second gas nozzle to form a gas stream;

a transport slot, said transport slot is collected said gas in said gas stream, and used as a channel to exhaust said gas stream; and

a gas-extracting apparatus, said gas-extracting apparatus is connected with said transport slot by using a third tube, wherein said gas suppler and said gas-exhausting apparatus must be opened continuously in said measuring process.

Claim 2 (Previously presented). The measuring system of a gas-stream environment according to claim 1, further comprising a first flow rate regulating valve fixing on said first gas nozzle.

Claim 3 (Previously presented). The measuring system of a gas-stream environment according to claim 1, further comprising a second flow rate regulating valve fixing on said second gas nozzle.

Claim 4 (Previously presented). The measuring system of a gas-stream environment according to claim 1, wherein said gas-extracting apparatus comprises a gas-extracting motor.

Claim 5 (Previously presented). The measuring system of a gas-stream environment according to claim 1, wherein said gas-extracting apparatus comprises a venture structure.

Claim 6 (Previously presented). The measuring system of a gas-stream environment according to claim 1, wherein said gas is an inert gas.

Claim 7 (Previously presented). The measuring system of a gas-stream environment according to claim 1, wherein said gas is nitrogen.

Claim 8 (Cancelled).

Claim 9 (Currently amended). A measuring system of a gas-stream environment, said measuring system of a gas-stream environment comprising:

a stage, said stage is located on a transport apparatus and a wafer placed on said stage;

a datum platen, said datum platen is located on said transport apparatus and on a side of said stage to place a datum slice;

a lens, said lens is located above said stage that is used to measure the thickness of said wafer and said datum slice;

a gas supplier, said gas supplier is used to supply a gas;

a first gas nozzle, said first gas nozzle is located on a side of said datum platen;

a second gas nozzle, said second gas nozzle is located on a side of said stage;

a first tube, said first tube is connected with said first gas nozzle and with said supplier;

a second tube, said second tube is connected with said second gas nozzle and with said gas supplier, wherein said gas supplier must be opened to supplied make said gas passed through said first tube and said second tube, and exhausted from said first gas nozzle and said second gas nozzle to form a gas stream;

a transport slot, said transport slot is extracted said gas; and

a gas-extracting apparatus, said gas-extracting apparatus is connected with said transport slot by using a third tube, wherein said gas suppler and said gas-exhausting apparatus must be opened continuously in said measuring process.

Claim 10 (Previously Presented). The measuring system of a gas-stream environment according to claim 9, wherein said first tube comprises a first flow rate regulating valve.

Claim 11 (Previously Presented). The measuring system of a gas-stream environment according to claim 9, wherein said second tube comprises a second flow rate regulating valve.

Claim 12 (Previously Presented). The measuring system of a gas-stream environment according to claim 9, wherein said gas-extracting apparatus comprises a gas-extracting motor.

Claim 13 (Previously Presented). The measuring system of a gas-stream environment according to claim 9, wherein said gas-extracting apparatus comprises a venture structure.

Claim 14 (Previously Presented). The measuring system of a gas-stream environment according to claim 9, wherein said gas is an inert gas.

Claim 15 (Previously Presented). The measuring system of a gas-stream environment according to claim 9, wherein said gas is a nitrogen.

Claim 16 (Cancelled).

Claim 17 (Previously Presented). A measuring system of a gas-stream environment, said measuring system comprising:

a stage, said stage is located on a transport apparatus and a wafer placing on said stage;

a datum platen, said datum platen is located on said transport apparatus and on a side of said stage to place a datum slice;

a lens, said lens is located above said stage that is used to measure the thickness of said wafer and said datum slice;

a gas supplier, said gas supplier is used to supply a gas in a gas stream;

a first gas nozzle, said first gas nozzle is located on a side of said datum platen and on said transport apparatus to exhaust said gas;

a second gas nozzle, said second gas nozzle is located on a side of said stage and on said transport apparatus to exhaust said gas in said gas stream;

a first tube, said first tube having a first flow rate regulating valve, and is connected with said first gas nozzle and with said gas supplier;

a second tube, said second tube having a second flow rate regulating valve and is connected with said second gas nozzle and with said gas supplier, wherein said gas supplier must be opened to make said gas that passed through said first tube and said second tube, and exhausted from said first gas nozzle and said second gas nozzle to form a gas stream;

a transport slot, said transport slot is an opening to exhaust said gas; and

a gas-extracting apparatus, said gas-extracting apparatus is connected with said transport slot by using a third tube and is produced an attraction to remove said gas, wherein said gas supplier and said gas-exhausting apparatus must be opened continuously in said measuring process.

Claim 18 (Previously Presented). The measuring system of a gas-stream environment according to claim 17, wherein said gas-extracting apparatus comprises a venture structure.

Claim 19 (Previously Presented). The measuring system of a gas-stream environment according to claim 17, wherein said gas is an inert gas.

Claim 20 (Previously Presented). The measuring system of a gas-stream environment according to claim 17, wherein said gas is nitrogen.

Claim 21 (Previously Presented). The measuring system of a gas-stream environment according to claim 1, wherein said first gas nozzle used to exhaust a gas in a gas stream.

Claim 22 (Previously Presented). The measuring system of a gas-stream environment according to claim 1, wherein said transport slot used collect said gas in said gas stream.

Claim 23 (Previously Presented). The measuring system of a gas-stream environment according to claim 1, wherein said transport slot used to be a channel to exhaust said gas in said gas stream.

Claim 24 (Previously Presented). The measuring system of a gas-stream environment according to claim 1, wherein the step of said lens located above said stage to measure said thickness of said wafer comprises:

placing said wafer on said stage by using a robot;  
moving said stage to the place under said lens by using said transport device;  
irradiating a light from said lens to a surface of said wafer and the data, wherein said data returned from said light and showed on a monitor; and  
analyzing said data to obtain said thickness of said wafer.

Claim 25 (Previously Presented). The measuring system of a gas-stream environment according to claim 9, wherein the step of said lens located above said stage to measure said thickness of said wafer comprises:

placing said wafer on said stage by using a robot;

moving said stage to the place under said lens by using said transport device;

irradiating a light from said lens to a surface of said wafer and the data, wherein said data returned from said light and showed on a monitor; and

analyzing said data to obtain said thickness of said wafer.

Claim 26 (Previously Presented). The measuring system of a gas-stream environment according to claim 17, wherein the step of said lens located above said stage to measure said thickness of said wafer comprises:

placing said wafer on said stage by using a robot;

moving said stage to the place under said lens by using said transport device;

irradiating a light from said lens to a surface of said wafer and the data, wherein said data returned from said light and showed on a monitor; and

analyzing said data to obtain said thickness of said wafer.